

L Number	Hits	Search Text	DB	Time stamp
1	181	(thin adj film adj transistors) near10 (pixel adj (unit or region or area))	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/04/14 13:26
2	0	(signal adj lines) near10 (crossing or perpendicular) near10 (gate adj lines) and ((thin adj film adj transistors) near10 (pixel adj (unit or region or area)))	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/04/14 13:28
3	0	(signal adj lines) near10 (crossing or perpendicular) near10 (scan adj lines) and ((thin adj film adj transistors) near10 (pixel adj (unit or region or area)))	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/04/14 13:29
6	2	6043145.did.	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/04/14 13:35
-	22	"349" and (first adj photoresist adj layer)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/04/11 13:32
-	23	"349" and (second adj photoresist adj layer)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/04/11 13:33
-	2	"349" and (third adj photoresist adj layer)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/04/11 13:34
-	2	("349" and (first adj photoresist adj layer)) and ("349" and (second adj photoresist adj layer)) and ("349" and (third adj photoresist adj layer))	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/04/11 13:49
-	1811	first adj photoresist adj layer	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/04/11 13:51
-	1873	second adj photoresist adj layer	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/04/11 13:52
-	365	third adj photoresist adj layer	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/04/11 13:53
-	264	(first adj photoresist adj layer) and (second adj photoresist adj layer) and (third adj photoresist adj layer)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/04/11 13:54
-	1	(first adj photoresist adj layer) near10 cover near10 pixel	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/04/11 13:57
-	0	(first adj photoresist adj layer) near10 above near10 pixel	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/04/11 13:58

-	1	(first adj photoresist adj layer) near10 over near10 pixel	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/04/11 14:06
-	413	(contact or hole or opening or aperture) near10 (first adj photoresist adj layer)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/04/11 14:08
-	399	(contact or hole or opening or aperture) near10 (second adj photoresist adj layer)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/04/11 14:09
-	65	(contact or hole or opening or aperture) near10 (third adj photoresist adj layer)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/04/11 14:10
-	26	((contact or hole or opening or aperture) near10 (first adj photoresist adj layer)) and ((contact or hole or opening or aperture) near10 (second adj photoresist adj layer)) and ((contact or hole or opening or aperture) near10 (third adj photoresist adj layer))	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/04/11 14:14
-	699	(349/43).CCLS.	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/04/11 14:15
-	1	349/43 and ((first adj photoresist adj layer) near10 (hole or opening or aperture or contact))	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/04/11 14:18
-	0	349/43 and ((second adj photoresist adj layer) near10 (hole or opening or aperture or contact))	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/04/11 14:19
-	0	(first adj photoresist adj layer) near10 expos\$6 near10 (drain adj electrode)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/04/11 14:21
-	0	(first adj photoresist adj layer) near10 exposing near10 (drain adj electrode)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/04/11 14:22
-	0	(second adj photoresist adj layer) near10 exposing near10 (drain adj electrode)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/04/11 14:22
-	1	(first adj photoresist adj layer) near10 exposing near10 (thin adj film adj transistor)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/04/11 14:24
-	1	(photoresist adj layers) near10 expos\$6 near10 (drain adj electrode)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/04/11 14:34

-	2	(photoresist adj layers) near10 expos\$6 near10 (thin adj film adj transistor)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/04/11 14:29
-	0	(first adj photoresist) near10 expos\$6 near10 (drain adj electrode)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/04/11 14:31
-	2	(first adj photoresist) near10 expos\$6 near10 (thin adj film adj transistor)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/04/11 14:31
-	2	6063653.did.	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/04/11 14:40
-	1	(first adj photoresist) near10 cover\$6 near10 (pixel)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/04/11 14:42
-	7	(first adj photoresist) near10 (above or over or overlay) near10 (pixel)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/04/11 14:43
-	8	(second adj photoresist) near10 (above or over or overlay) near10 (pixel)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/04/11 14:45
-	0	(third adj photoresist) near10 (above or over or overlay) near10 (pixel)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/04/11 14:57
-	6	((first adj photoresist) near10 (above or over or overlay) near10 (pixel)) and ((second adj photoresist) near10 (above or over or overlay) near10 (pixel))	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/04/11 16:50
-	1	(third adj photoresist) near10 (cover or on) near10 (pixel)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/04/11 14:58
-	861	photoresist near10 expos\$6 near10 drain	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/04/11 15:06
-	35	(first adj photoresist) near10 expos\$6 near10 drain	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/04/11 15:00
-	54	(second adj photoresist) near10 expos\$6 near10 drain	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/04/11 15:01
-	10	(photoresist near10 expos\$6 near10 drain) and ((first adj photoresist) near10 expos\$6 near10 drain) and ((second adj photoresist) near10 expos\$6 near10 drain)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/04/11 15:01

-	932	(first adj photoresist) near10 (hole or opening or aperture or contact or slit or via)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/04/11 15:09
-	953	(second adj photoresist) near10 (hole or opening or aperture or contact or slit or via)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/04/11 15:11
-	152	(third adj photoresist) near10 (hole or opening or aperture or contact or slit or via)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/04/11 15:11
-	50	((first adj photoresist) near10 (hole or opening or aperture or contact or slit or via)) and ((second adj photoresist) near10 (hole or opening or aperture or contact or slit or via)) and ((third adj photoresist) near10 (hole or opening or aperture or contact or slit or via))	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/04/11 15:25
-	89	holes near10 (photoresist adj (films or layers))	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/04/11 15:29
-	1	holes near10 (photoresist adj (films or layers)) near10 expos\$6 near10 (drain adj electrode)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/04/11 15:29
-	0	holes near10 (photoresist adj (films or layers)) near10 expos\$6 near10 (TFT)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/04/11 15:30
-	0	(holes or vias or contacts or apertures or slits or openings) near10 (photoresist adj (films or layers)) near10 expos\$6 near10 (TFT)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/04/11 15:31
-	1	(holes or vias or contacts or apertures or slits or openings) near10 (photoresist adj (films or layers)) near10 expos\$6 near10 (drain adj electrode)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/04/11 15:39
-	19	photoresist near10 exposing near10 (drain adj electrode)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/04/11 15:51
-	1	photoresist near10 holes near10 exposing near10 (drain adj electrode)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/04/11 15:44
-	4	349/43 and (photoresist adj (films or layers))	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/04/11 15:56
-	1	(photoresist adj (films or layers)) near10 expos\$6 near10 (drain adj electrode) near10 (through adj hole)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/04/11 15:57

-	0	(photoresist adj (films or layers)) near10 contact near10 (drain adj electrode) near10 (hole)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/04/11 15:58
-	0	(photoresist adj (films or layers)) near10 opening near10 (drain adj electrode)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/04/11 15:59
-	0	(photoresist adj (films or layers)) near10 showing near10 (drain adj electrode)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/04/11 16:00
-	2	(photoresist adj (films or layers)) near10 expos\$6 near10 (thin adj film adj transistor)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/04/11 16:03
-	0	(photosensitive adj (films or layers)) near10 expos\$6 near10 (drain adj electrode)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/04/11 16:04
-	0	(photosensitive adj resins) near10 expos\$6 near10 (drain adj electrode)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/04/11 16:04
-	15	(photosensitive) near10 expos\$6 near10 (drain adj electrode)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/04/11 16:05
-	7	(passivation adj layers) near10 expos\$6 near10 (drain adj electrode)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/04/11 16:07
-	11	(first adj passivation adj layer) near10 expos\$6 near10 (drain adj electrode)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/04/11 16:08
-	7	(second adj passivation adj layer) near10 expos\$6 near10 (drain adj electrode)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/04/11 16:23
-	1	(third adj passivation adj layer) near10 expos\$6 near10 (drain adj electrode)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/04/11 16:10
-	6	((first adj passivation adj layer) near10 expos\$6 near10 (drain adj electrode)) and ((second adj passivation adj layer) near10 expos\$6 near10 (drain adj electrode))	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/04/11 16:15
-	0	(first adj photosensitive adj (layer or film)) near10 expos\$6 near10 (drain adj electrode)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/04/11 16:13
-	0	(first adj resin adj (layer or film)) near10 expos\$6 near10 (drain adj electrode)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/04/11 16:15

-	0	(first adj photoresist) near10 (drain adj contact adj hole)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM TDB	2003/04/11 16:16
-	0	(first adj photoresist) near10 cover near10 (first adj pixel adj (group or area))	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM TDB	2003/04/11 16:27
-	0	(first adj photoresist) near10 cover near10 (first adj pixel)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM TDB	2003/04/11 16:28
-	1	(photoresist adj (films or layers)) near10 (pixel adj areas)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM TDB	2003/04/11 16:29
-	0	(photoresist adj (films or layers)) near10 (pixel adj groups)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM TDB	2003/04/11 16:31
-	1	(photoresist adj (films or layers)) near10 cover near10 pixel	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM TDB	2003/04/11 16:33
-	152	first adj pixel adj (group or area)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM TDB	2003/04/11 16:35
-	106	second adj pixel adj (group or area)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM TDB	2003/04/11 16:36
-	21	third adj pixel adj (group or area)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM TDB	2003/04/11 16:36
-	14	(first adj pixel adj (group or area)) and (second adj pixel adj (group or area)) and (third adj pixel adj (group or area))	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM TDB	2003/04/11 16:41
-	2	20020075435.did.	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM TDB	2003/04/11 16:41
-	2	4673253.did.	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM TDB	2003/04/11 16:53
-	12	(first adj photoresist) near10 pixel	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM TDB	2003/04/11 16:54
-	27	(second adj photoresist) near10 pixel	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM TDB	2003/04/11 16:55

-	7	(third adj photoresist) near10 pixel	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/04/11 16:55
-	5	((first adj photoresist) near10 pixel) and ((second adj photoresist) near10 pixel) and ((third adj photoresist) near10 pixel)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/04/11 17:11
-	0	(pixel adj area) near10 cover near10 (photoresist adj (films or layers))	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/04/11 17:13
-	0	(pixel adj area) near10 under near10 (photoresist adj (films or layers))	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/04/11 17:14
-	0	(pixel adj unit) near10 under near10 (photoresist adj (films or layers))	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/04/11 17:14
-	0	(pixel adj group) near10 under near10 (photoresist adj (films or layers))	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/04/11 17:14
-	0	(pixel adj section) near10 under near10 (photoresist adj (films or layers))	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/04/11 17:15
-	0	(pixel) near10 under near10 (photoresist adj (films or layers))	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/04/11 17:15
-	0	(pixel) near10 under near10 (photosensitive adj (films or layers))	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/04/11 17:19
-	0	(pixel) near10 under near10 (etching adj (films or layers))	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/04/11 17:20
-	0	(etching adj (films or layers)) near10 over near10 pixels	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/04/11 17:21
-	1	etchant near10 over near10 pixels	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/04/11 17:26
-	1	(mask adj layers) near10 over near10 pixels	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/04/11 17:35
-	0	(resist adj layers) near10 over near10 pixels	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/04/11 17:35

-	0	(pixel adj areas) near10 (resist adj layers)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM TDB	2003/04/11 17:36
-	5272	(pixel) near10 under ((first adj photoresist adj layer) near10 above near10 pixel) near10 (resist adj layers)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM TDB	2003/04/11 17:38
-	0	(pixel) near10 under near10 (resist adj layers)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM TDB	2003/04/11 17:39
-	0	(pixel) near10 under near10 (platings)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM TDB	2003/04/11 17:39
-	0	(pixel) near10 under near10 (DFRs)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM TDB	2003/04/11 17:40
-	0	((multiple or plural) adj (pixel adj layers)) near10 (contact or hole or aperture or slit or opening)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM TDB	2003/04/14 09:31
-	2	((multiple or plural) adj (pixel adj layers))	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM TDB	2003/04/14 09:33
-	2	((multiple or plural) near10 (pixel adj layers))	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM TDB	2003/04/14 09:36
-	2	multiple adj pixel adj layers	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM TDB	2003/04/14 09:40
-	0	plural adj pixel adj layers	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM TDB	2003/04/14 09:41
-	3	(spacer or protrusion) near10 pierc\$6 near10 layers	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM TDB	2003/04/14 09:42
-	6	(spacer or pillar) near10 pierc\$6 near10 layers	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM TDB	2003/04/14 09:49
-	53	pixel adj layers	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM TDB	2003/04/14 10:18
-	0	(pixel adj layers) near10 expos\$6 near10 (drain adj electrode)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM TDB	2003/04/14 09:54

-	0	(pixel adj layers) near10 (drain adj electrode)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/04/14 09:54
-	0	(pixel adj layers) near10 expos\$6 near10 (data adj line)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/04/14 09:57
-	0	(photoresist adj layers) near10 expos\$6 near10 (data adj line)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/04/14 09:58
-	0	(photomask adj layers) near10 expos\$6 near10 (data adj line)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/04/14 09:58
-	0	(resist adj layers) near10 (pixel adj layers)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/04/14 10:00
-	0	(resist adj layers) near10 (exposing) near10 (drain adj electrode)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/04/14 10:00
-	3	(first adj insulating adj layer) near10 cover\$6 Near10 (pixel adj electrode)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/04/14 10:24
-	13	(second adj insulating adj layer) near10 cover\$6 Near10 (pixel adj electrode)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/04/14 10:23
-	3	(third adj insulating adj layer) near10 cover\$6 Near10 (pixel adj electrode)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/04/14 10:23
-	0	((first adj insulating adj layer) near10 cover\$6 Near10 (pixel adj electrode)) and ((second adj insulating adj layer) near10 cover\$6 Near10 (pixel adj electrode)) and ((third adj insulating adj layer) near10 cover\$6 Near10 (pixel adj electrode))	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/04/14 10:23
-	17	(first adj insulating adj (layer or film)) near10 cover\$6 near10 (pixel adj electrode)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/04/14 10:25
-	33	(second adj insulating adj (layer or film)) near10 cover\$6 near10 (pixel adj electrode)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/04/14 10:25
-	6	(third adj insulating adj (layer or film)) near10 cover\$6 near10 (pixel adj electrode)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/04/14 10:26

-	1	((first adj insulating adj (layer or film)) near10 cover\$6 near10 (pixel adj electrode)) and ((second adj insulating adj (layer or film)) near10 cover\$6 near10 (pixel adj electrode)) and ((third adj insulating adj (layer or film)) near10 cover\$6 near10 (pixel adj electrode))	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/04/14 10:37
-	1	(conducting adj (film or layer)) near10 (insulating adj layers) near10 connect\$6 near10 (drain or data)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/04/14 10:42
-	10	(metal) near10 (insulating adj layers) near10 connect\$6 near10 (drain or data)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/04/14 10:44
-	196	(metal) near10 (over or on or above) near10 (insulating adj layers)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/04/14 10:46
-	0	(metal) near10 (over or on or above) near10 (insulating adj layers)near10 connect near10 (drain electrode)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/04/14 10:47
-	12	(metal) near10 (over or on or above) near10 (insulating adj layers)near10 (drain electrode)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/04/14 11:06
-	0	((passivation or protective) adj (layer or film)) near10 between near10 (first adj insulating adj (film or layer)) near10 TFT	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/04/14 11:11
-	22	((passivation or protective) adj (layer or film)) near10 between near10 (first adj insulating adj (film or layer))	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/04/14 11:53
-	0	(first adj insulating adj (film or layer)) near10 cover near10 (first adj pixel)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/04/14 11:14
-	46	(signal adj lines) near10 (crossing or perpendicular) near10 (gate adj lines)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/04/14 13:34
-	134	switching near10 (pixel adj area)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/04/14 11:56
-	0	((signal adj lines) near10 (crossing or perpendicular) near10 (gate adj lines)) and (switching near10 (pixel adj area))	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/04/14 11:56
-	411	switching near10 (pixel adj (area or unit or region))	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/04/14 11:57

-	0	((signal adj lines) near10 (crossing or perpendicular) near10 (gate adj lines)) and (switching near10 (pixel adj (area or unit or region)))	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/04/14 11:57
-	82	switch near10 (pixel adj (area or unit or region))	USPÄT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/04/14 11:58
-	0	((signal adj lines) near10 (crossing or perpendicular) near10 (gate adj lines)) and (switch near10 (pixel adj (area or unit or region)))	USPÄT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/04/14 13:24